

Toxic and bulk gases used in semiconductor production at one facility

CHEMICAL NAME	QUANTITY
10% Phosphine	380 Cu Ft
10% Phosphine in Nitrogen and argon	1700 Cu Ft
100 ppm Diborane in Hydrogen	407 Cu Ft
Acetylene	200 Cu Ft
Ammonia	3025 Cu Ft
Argon	4276 Cu Ft
Boron Trifluoride	2 Cu Ft
Carbon Dioxide	1000 Cu Ft
Chlorine	280 Cu Ft
Dichlorosilane	1730 Cu Ft
dissolved Arsine	1812 Cu Ft
Freon 116	350 Cu Ft
Freon 14	750 Cu Ft
Freon 23	1277 Cu Ft
Freon R-23	200 Cu Ft
Halocarbon 14	398 Cu Ft
Helium	2350 Cu Ft
Hydrogen	1900 Cu Ft
Hydrogen Chloride	3568 Cu Ft
Hydrogen Chloride	700 Cu Ft
Liquid Hydrogen	5200 Gal
Liquid Nitrogen	10700 Gal
Liquid Oxygen	2700 Gal
Nitrogen	10010 Cu Ft
Nitrous Oxide	4000 Cu Ft
Oxygen	4900 Cu Ft
Propane	3600 Cu Ft
Silane	1602 Cu Ft
Silicon Tetrachloride	1000 Cu Ft
Sulfur Hexafluoride	1122 Cu Ft
Source: Mountain View, CA Fire Dept., 1999	
Gases from one semiconductor fabrication facility	